

(19) United States

(12) Patent Application Publication (10) Pub. No.: US 2024/0213053 A1 Park et al.

Jun. 27, 2024 (43) Pub. Date:

(54) VALVE STRUCTURE AND SUBSTRATE PROCESSING APPARATUS INCLUDING THE

(71) Applicant: Samsung Electronics Co., Ltd.,

Suwon-si (KR)

(72) Inventors: Kangmin Park, Suwon-si (KR);

Hyungho Kim, Suwon-si (KR); Dongwoo Wi, Hwaseong-si (KR); Hyunsoo Chun, Suwon-si (KR); Jiho

Uh, Suwon-si (KR)

(21) Appl. No.: 18/601,017

(22) Filed: Mar. 11, 2024

Related U.S. Application Data

Continuation of application No. 17/747,270, filed on May 18, 2022, now Pat. No. 11,948,814.

(30)Foreign Application Priority Data

(KR) 10-2021-0144013 Oct. 26, 2021

Publication Classification

(51) **Int. Cl.** H01L 21/67 (2006.01)F16K 3/02 (2006.01) F16K 3/18 (2006.01)F16K 3/314 (2006.01)F16K 51/02 (2006.01)H01L 21/677 (2006.01)

(52)U.S. Cl.

> CPC H01L 21/67126 (2013.01); F16K 51/02 (2013.01); H01L 21/67017 (2013.01); H01L 21/67739 (2013.01); F16K 3/0281 (2013.01); F16K 3/18 (2013.01); F16K 3/314 (2013.01)

(57)ABSTRACT

A process chamber door for closing or opening an entrance of a process chamber through which a substrate to be process is loaded includes a seal plate including a front surface and a rear surface opposite to each other in a first direction, a connection block connected to the rear surface of the seal plate and including a central portion and two side portions connected to the rear surface of the seal plate, and a shaft connected to the central portion of the connection block. The connection block includes a first hinge groove and a second hinge groove. The first hinge groove is exposed at a bottom surface and a side surface of the connection block and the second hinge groove is exposed at an upper surface and the side surface of the connection block.

